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inner walls of the reaction chamber, wherein at least one of said electrode insulating member, said electrostatic chuck, said focus ring and said covering member is constituted of the plasma-resistant member defined in Claim 1.

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7. (Amended) A plasma treating apparatus comprising an electrode insulating member for insulation between an upper electrode and a reaction chamber, an electrostatic chuck for electrostatically attracting and holding a body to be treated by application of a high voltage to an electric conductor member thereof, a focus ring provided in the vicinity of the upper electrode or lower electrode for effectively transmitting reactive ions toward the treating surface of said body to be treated, and a covering member for covering the inner walls of the reaction chamber, wherein at least one of said electrode insulating member, said electrostatic chuck, said focus ring and said covering member is constituted of the plasma-resistant member defined in Claim 2.
